

## Refine Search

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### Search Results -

Terms	Documents
(plasma same (hydrogen and nitrogen)) and (plasma with etch\$5) and ((resist or mask or photoresist) with selectiv\$4)	762

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**Database:** US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
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 Derwent World Patents Index  
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**Search:** L1

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### Search History

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*DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR*

L1    (plasma same (hydrogen and nitrogen)) and (plasma with etch\$5) and  
 ((resist or mask or photoresist) with selectiv\$4)

762    L1

END OF SEARCH HISTORY